

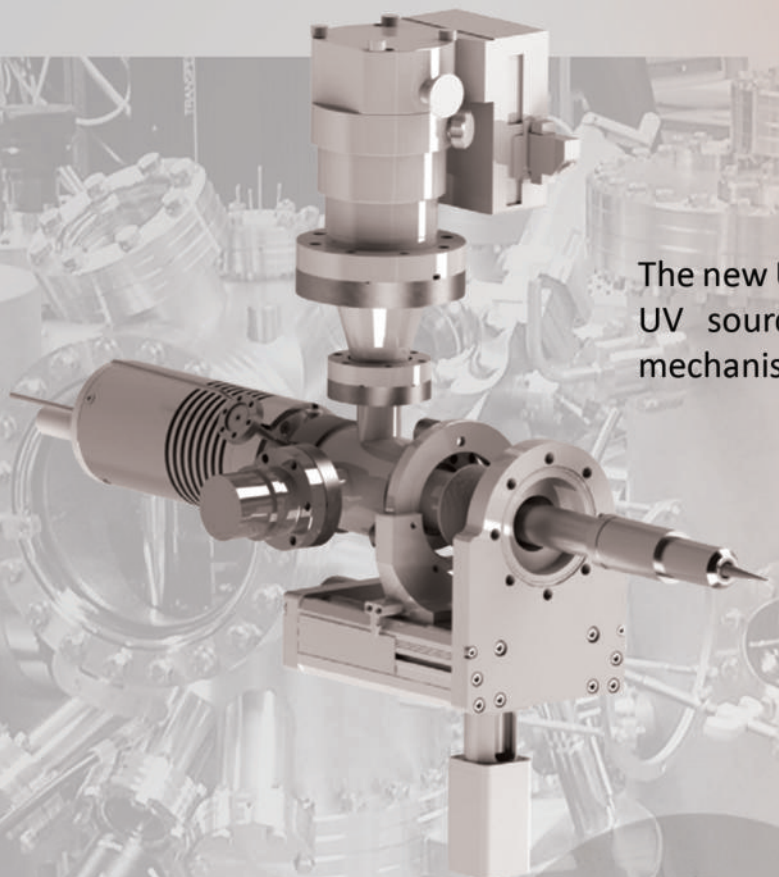


OmniVac

Surface Analysis and Vacuum Technology

Ultraviolet Source

UVS 1000



The new UVS 1000 is an ultra-high efficiency UV source based on plasma local field mechanism and solid RF source technology.

■ multiple working gases
He, Ne, Ar, Kr, Xe

■ photon energy
8.4 eV-40.8 eV (30 nm- 147 nm)

■ photon flux $> 5 \cdot 10^{17}$ photons/Sr sec

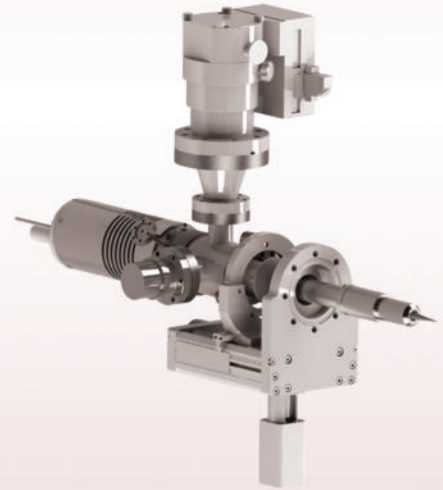
■ resolution < 1 meV

■ bakeable to 120°C

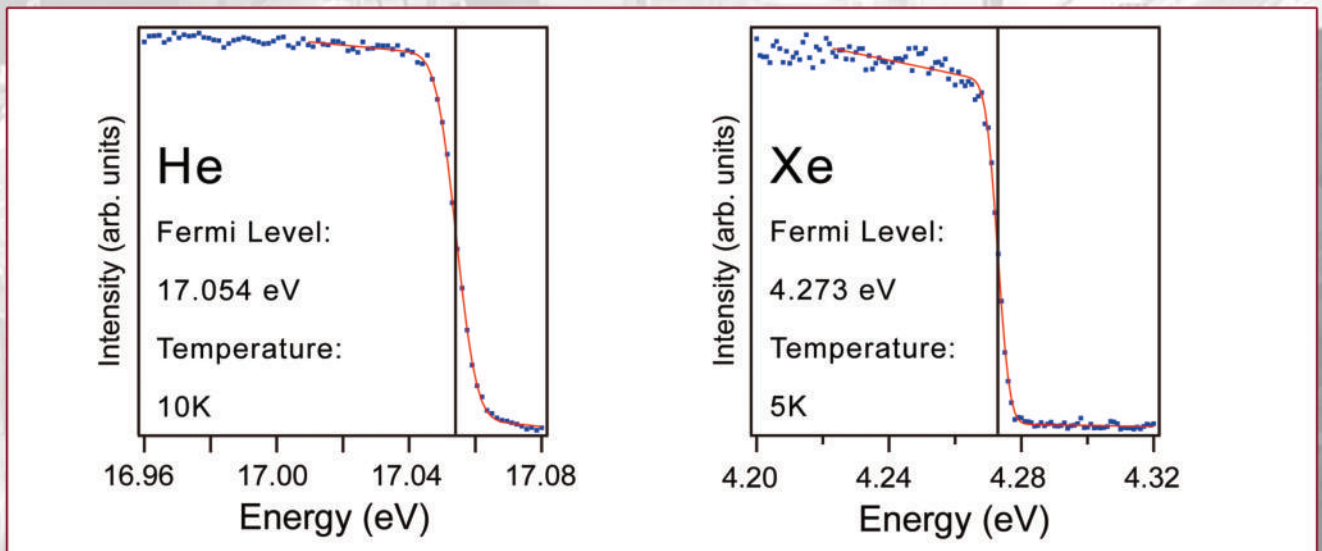
www.omnivac.de

UVS 1000 Ultraviolet Source

The new UVS 1000 is an ultra-high efficiency UV source based on plasma local field mechanism and solid RF source technology. It provides orders of magnitude higher efficiency than traditional plasma-based UV sources. The UVS 1000 is an electrode-free and ignition-free universal UV source, which can work with various gases and gas mixtures. It opens access to a broad range of applications, such as photoemission spectroscopy, mass spectroscopy, atomic absorption spectroscopy etc.



Spectrum excited by He and Xe radiation



PS-UVS 1000

- compact solid RF source driven by 24 V / 200 W power source

Related products:

- PS-UVS 1000 power supply
- leak valve (for gas inlet)
- pumping lines for optional differential pumping
- linear shift

- ▶ multiple working gases
He, Ne, Ar, Kr, Xe
- ▶ photon energy
8.4 eV-40.8 eV (30 nm- 147 nm)
- ▶ photon flux $> 5 \cdot 10^{17}$ photons/Sr sec
- ▶ resolution < 1 meV
- ▶ bakeable to 120°C



OmniVac
Hertelsbrunnenring 30
D-67657 Kaiserslautern / Germany

Tel +49 (0) 631 3110740
Fax +49 (0) 631 28056
sales@omnivac.de